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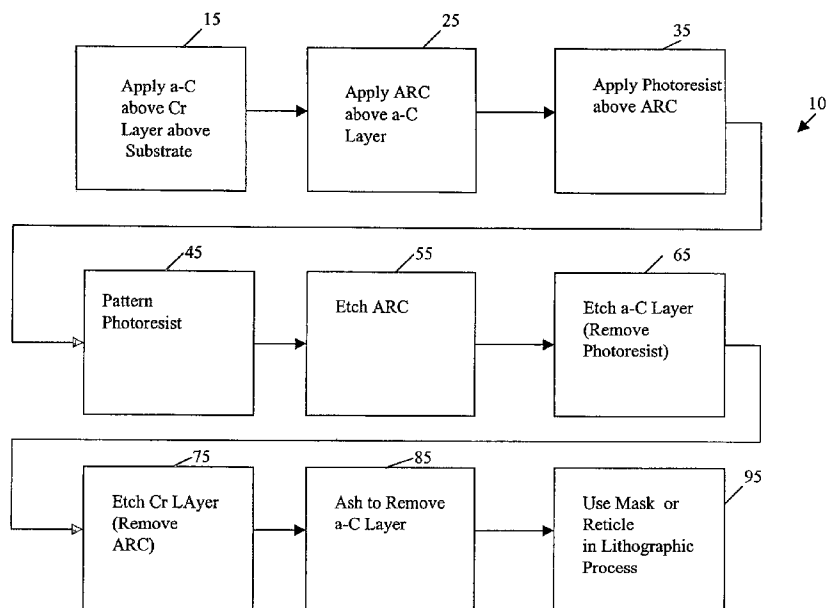
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(54) Title: METHOD OF USING AN AMORPHOUS CARBON LAYER FOR IMPROVED RETICLE FABRICATION



(57) Abstract: A method of using an amorphous carbon layer (130) for improved reticle fabrication includes depositing a stack of layers including a substrate (110), an absorber (120), a transfer layer (130), an antireflective coating (ARC) layer (140), and a photoresist layer (150), patterning (45) the photoresist layer (150), and etching (55, 65) the ARC layer (140) and the transfer layer (130). The method also includes etching (75) the absorber layer (120) and removing (85) the transfer layer (130). The transfer layer (130) including amorphous carbon.

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